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Mask

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Description

(1) FIG. 1 is a front perspective view of a mask, showing my new design;

(2) FIG. 2 is a front view thereof;

(3) FIG. 3 is a rear view thereof;

(4) FIG. 4 is a left side view thereof;

(5) FIG. 5 is a right side view thereof;

(6) FIG. 6 is a top view thereof; and,

(7) FIG. 7 is a bottom view thereof.

(8) The broken lines in the drawings illustrate the portions of the mask, which form no part of the claimed design.

Claims

The ornamental design for a mask, as shown and described.
